



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Kazuyuki NITTA et al.

Serial No. 09/987,718

Filed November 15, 2001

METHOD FOR FORMING A HOLE-
PATTERNED PHOTORESIST LAYER

: MAIL STOP AFTER FINAL

: Docket No. 2001_1703A

: Group Art Unit 1756

: Examiner K. Sagar

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FEB 09 2004

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RESPONSE UNDER 37. CFR 1.116

EXPEDITED PROCEDURE

EXAMINING GROUP 1756

RESPONSE TO FINAL REJECTION

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

This is in response to the Final Rejection dated November 4, 2003.